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## (54) PHOTOSENSITIVE RESIN COMPOSITION AND PRODUCTION OF PHOTOSENSITIVE FILM AND FLUORESCENT PATTERN USING SAME

### (57) Abstract:

PROBLEM TO BE SOLVED: To obtain a resin compsn. not increasing its viscosity over a long period of time and excellent in shelf stability by incorporating a specified phosphor, a specified resin, a photopolymerizable unsatd. compd. and a photo- initiator. SOLUTION: This resin compsn. contains a phosphor (A) surface-treated with a compd. having a carboxyl group, a resin (B) having carboxyl groups, a photopolymerizable unsatd. compd. (C) having an ethylenically unsatd. group and a photo-initiator (D) generating free radicals when irradiated with active light. The phosphor A is obtd. usually by surfacetreating a metal oxide-base phosphor with a compd. having a carboxyl group. The resin B is obtd. by copolymerizing unsatd. carboxylic acid with one or more kinds of other unsatd.

monomers each copolymerizable with the carboxylic acid. Any known photopolymerizable

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